

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Karola Richter et al.

JC20 Rec'd PCT/PTO 1 4 OCT 2005

Serial No:

Filing Date:

Title: SILICON SUBSTRATE COMPRISING POSITIVE ETCHING PROFILES
WITH A DEFINED SLOPE, ANGLE, AND PRODUCTION METHOD

Examiner:

Art Unit:

October 12, 2005

HMP201S1

INFORMATION DISCLOSURE STATEMENT
UNDER 37 CFR § 1.97.

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

SIR:

Applicants are respectfully submitting a copy of International Search Report dated November 17, 2004 and PCT SCHRIFTLICHER BESCHEID DER INTERNATIONALEN RECHERCHENBEHÖRDE issued by European Patent Office Berlin and copies of patent documents cited in the International Search Report of the instant application.

The following is a listing of the references in question.

- US 6 198 150
- US 6 180 466
- DE 197 36 370
- EP 0 822 582
- DE 42 41 045
- VOLLAND et al., Dry etching with gas chopping without rippled sidewalls,
Journal of Vacuum Science & Technology , November 1999

Applicants are respectfully submitting a form PTO-1449 with all references listed therein and including citation in the application. 1020 Rec'd PCT/PTO 14 OCT 2005

The above recited references taken alone or in combination are believed neither to anticipate or to render obvious the present application.

Consideration of the reference document during the examination of the present application is respectfully requested.

Respectfully submitted,
Karola Richter et al.

By: Horst M. Kasper
Horst M. Kasper, their attorney,
13 Forest Drive, Warren, N.J. 07059
Tel.: (908) 526-1717 Fax: (908) 526-6977
Reg. No. 28,559; Docket No.: HMP201

/sn-

Form PTO-1449

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)

HMP201

Sheet 1 of 3
807553728

Applicant

RICHTER et al.

Filing Date

Group Art Unit

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	61198150	03/08/01	GELZINIS	H01L	29/00	
	6180466	01/30/01	IBOK	H01L	21/336	

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
	19736370	03/04/99	GERMANY	H01L	21/365		
	4241045	05/26/94	GERMANY	C27F	4/00		
	0822582	02/04/88	EPO	H01L	21/306		

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

	AVOLLAND B et al; "Dry etching with gas chopping without rippled sidewalls"; JOURNAL OF VACUUM SCIENCE & TECHNOLOGY, B: MICROELECTRONICS AND NANOMETER STRUCTURES; NOVEMBER 1999 VOLUME 17, ISSUE 6, PAGES: 2768-2771
--	---

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

JC20 Rec'd PCT/PTO 1 4 OCT 2005

PTO/SB/08 (2-92)

Sheet 2 of 3

Form PTO-1449							
INFORMATION DISCLOSURE CITATION IN AN APPLICATION <i>(Use several sheets if necessary)</i>							
Docket Number (Optional) HMP 201	Application Number 807553728						
Applicant RICHTER et al.							
Filing Date	Group Art Unit						
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER		DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER		DATE	COUNTRY	CLASS	SUBCLASS	Translation YES NO
OTHER DOCUMENTS (<i>Including Author, Title, Date, Pertinent Pages, Etc.</i>)							
	J.P. JOHN et al.; J. ELECTROCHEM SOC. VOL. 140 No. 9 (1993) pp 2622 - 2625						
	H. SEIDEL et al.; J. ELECTROCHEM SOC., VOL. 137, No. 11, November 1990, pp 3612 - 3632						
	B. KIM et al.; J. ELECTROCHEM SOC. VOL. 145, No. 7 July 1998, pp 2498 - 2508						
EXAMINER	DATE CONSIDERED						
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.							

3 of 3
10/553720

Form PTO-1449

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

Document Number (Optional)

HMP 201

Applicant

RICHTER et al

Filing Date

Group Art Unit

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	H.v. Boeing, FUNDAMENTALS OF PLASMA CHEMISTRY AND TECHNOLOGY
	p. 174, The Research Institute of Plasma Chemistry, Carlsbad, CA
	J. W. RANGELOW et al; J. VAC. SCI. TECHNOL, B13(6)
	Nov/Dec 1995, pp 2394-2399
	K. M. CHANG et al; JOURNAL OF APPLIED PHYSICS
	SEPT 1, 1996, Vol. 80, Issue 5, pp 3048-3055

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.